



3651

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Akihiro OSAKA et al.

Application No.: 10/073,876

Filed: February 14, 2002

Docket No.: 105913.01

For: SEMICONDUCTOR MANUFACTURING METHOD AND SEMICONDUCTOR
MANUFACTURING APPARATUS

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PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 4, lines 20-26, delete current paragraph and insert therefor:

The invention of the first aspect is a semiconductor manufacturing method including a
~~step of detecting the position of the orientation flat or notch of a substrate and aligning to a~~
specific position, wherein a substrate transfer unit that transfers substrates to a processing
chamber or processing jig is used for the ~~orientation flat or notch alignment of the substrates.~~

Page 5, lines 6-10, delete current paragraph and insert therefor:

The invention of the second aspect is the semiconductor manufacturing method
~~according to the invention of the first aspect, wherein the orientation flat or notch alignment~~
of the substrates is performed in a transfer chamber in which the substrate transfer unit is
installed.

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AUG, 9, 2002

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